

*Amendment to the Specification*

Please amend the pending specification as follows.

[0001] This application is a continuation of U.S. Ser. No. 10/300,898 (now U.S. Patent 6,770,895 that issued August 3, 2004), filed November 21, 2002, entitled "Method and Apparatus for Isolating Light Source Gas from Main Chamber Gas in a Lithography Tool," which is incorporated by reference herein in its entirety.